



#5/AmctB NE  
4-11-03  
JQ

Attorney's Docket No. 42390P10606

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Qing Ma, Peng Cheng

Serial No. 09/894,334

Filed: June 27, 2001

For: SACRIFICIAL LAYER TECHNIQUE  
TO MAKE GAPS IN MEMS  
APPLICATIONS

Examiner: Coleman, William D.

Art Unit: 2823

Confirmation No.: 6477

AMENDMENT AND RESPONSE TO OFFICE ACTION

Box Amendments - No Fee.  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to an Office Action mailed January 24, 2003, please amend the above-identified application as follows, and consider the following remarks.

IN THE CLAIMS

Please cancel Claims 6 and 13 without prejudice or disclaimer.

Please amend the claims as follows:

1. (Twice Amended) A method comprising:  
over an area of a substrate, forming a plurality of three dimensional first structures;  
following forming the first structures, conformally introducing a sacrificial material over the area of the substrate;  
introducing a second structural material over the sacrificial material;  
exposing a portion of the sacrificial material;  
removing the sacrificial material; and

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PLEASE ENTER